EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	5436	((electrostatic) near3 (clamp$4 or force)) and electrode and dielectric·	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/09/08 13:35
L2	7197	((electrostatic) near3 (clamp$4 or force)) and electrode and dielectric	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 13:35
L3	5863	2 and (article or substrate or wafer or reticle or mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 13:41
L4	295	3 and (electrostatic near6 (mov$4 or driv$4) near5 (substrate or wafer or reticle or mask or article))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 13:51
L5	191	4 and (electrostatic near7 ((mov$4 or driv$4 or transport$4 or convey$4) near4 (substrate or reticle or mask or article or object or target)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 13:55
L6	39	5 and ("361"/$.ccls. or "355"/$.ccls. or "378"/$.ccls. or "310"/$.ccls. or "318"/$.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 14:01
L7	426	("20020008954"|"20020101956"|"20020109954"|"20020145714"|"20030155080"|"20040012767"|"4522489"|"4969168"|"5315473"|"5413360"|"5436790"|"5530616"|"5583786"|"5610683"|"5838529"|"5880922"|"6055150"|"6075375"|"6134096"|"6169652"|"6185085"|"6215642"|"6351367"|"6361313"|"6377060"|"6404483"|"6480369"|"6522519"|"6556414"|"6606234"|"6721035"|"6839217")".PN"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 14:01
L8	206	7 and ("361"/$.ccls. or "355"/$.ccls. or "378"/$.ccls. or "310"/$.ccls. or "318"/$.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 15:19

L9	0	(($4lithograph$4) and (electrode) and (dielectric adj3 (layer)) and (electrostatic near7 (provid$4 or integral$4) near6 (support$$ or base or chuck or position$4)) and ((mov$4 or driv$4 or remov$4) near5 (substrate or article or reticle or mask or object))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 15:28
L10	0	($6lithograph$4 and (handler same (provid$4 or position$4 or intergrat$4) near5 (chuck or base or support$4)) and electrostatic$4 and dielectric and ((mov$4 or remov$4 or driv$4) near5 (reticle or mask or substrate or wafer or article or object))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 15:34
L11	1	(((article or substrate or reticle or mask) near4 (handler)) near4 (provid$4 or position$4 or support$4) and detect$4 near5 (presence or absence) near4 (substrate or wafer or reticle or mask) and (electrostatic$4 near4 clamp$4)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 16:29